

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 06381P USA	SERIAL NO. 10/624 357
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Aaron Scott Lukas, et al.	
		FILING DATE 7/21/03	GROUP 2813

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
NB		4	6	0	3	1	6	8	7/29/1986	S. Sasaki, et al.	522	18	2/19/1985
NB		5	6	0	9	9	2	5	3/11/1997	R. C. Camilletti, et al.	427	503	12/4/1995
NB		5	9	7	0	3	8	4	10/19/1999	S. Yamazaki, et al.	438	795	8/2/1995
NB		6	0	1	7	8	0	6	1/25/2000	K. C. Harvey	438	475	7/28/1998
NB		6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
NB		6	1	6	8	9	8	0	1/2/2001	S. Yamazaki, et al.	438	162	9/26/1996
NB		6	2	8	4	0	5	0	9/4/2001	J. Shi, et al.	118	715	5/18/1998
NB	01	0	0	3	8	9	1	9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
NB	02	0	1	0	2	4	1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
NB	02	0	1	0	6	5	0	0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001
NB	02	0	1	4	2	5	8	5	10/3/2002	R. P. Mandal	438	633	3/4/2002
NB	03	0	0	3	2	3	0	0	2/13/2003	C. Waldfried, et al.	438	725	5/14/2001
NB	03	0	0	5	4	1	1	5	3/20/2003	R. Albano, et al.	427	487	9/14/2001

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
NB	WO	9	7	0	0	5	3	5		World			X	
NB	WO	02	0	6	5	5	3	4		World			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

NB		E. G. Parada, et al., "Improvement of Silicon Oxide Film Properties by Ultraviolet Excimer Lamp Annealing," Applied Surface Science 86, pp. 294-298 (1995).
NB		A. Guo, et al., "Highly Active Visible-Light Photocatalysts for Curing a Ceramic Precursor ¹ ," Chem Mater. 10, pp. 531-536 (1998).
NB		T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films," Chem. Mater. 12, pp. 3879-3884 (2000).
NB		M. Brinkmann, et al., "Room-Temperature Synthesis of a-SiO ₂ Thin Films by UV-Assisted Ozonolysis of a Polymer Precursor," Chem. Mater. 13, pp. 967-972 (2001).
NB		A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light," Chem. Mater. 12, pp. 3842-3847 (2000).
NB		M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes," Chem. Mater. 12, pp. 1591-1596 (2000).
NB		Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
NB		C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER

Nema Berezhny

DATE CONSIDERED

11-30-04

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.